

US00D526094S

(12) **United States Design Patent**
Chen

(10) **Patent No.:** **US D526,094 S**

(45) **Date of Patent:** **** Aug. 1, 2006**

(54) **MASK**

(76) **Inventor:** **Chun-Nan Chen**, 182, Haichung St.,
An Nan District, Tainan (TW)

(**) **Term:** **14 Years**

(21) **Appl. No.:** **29/233,630**

(22) **Filed:** **Jul. 7, 2005**

(51) **LOC (8) Cl.** **29-02**

(52) **U.S. Cl.** **D29/108**

(58) **Field of Classification Search** D29/102-110,
D29/122; 2/5, 6.1, 6.3, 6.5-6.7, 411, 414,
2/423-425, 431, 8-9, 427; 128/201.24, 206.21,
128/206.28; D24/110.1, 110.2, 110.3
See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

D317,063 S	*	5/1991	Johnson	D29/110
D373,224 S	*	8/1996	Pernicka et al.	D29/110
D384,441 S	*	9/1997	Badger	D29/110
D407,858 S	*	4/1999	Cyr et al.	D29/108
D412,376 S	*	7/1999	Jurga et al.	D29/106

6,176,239 B1	*	1/2001	Grove et al.	128/206.24
6,381,749 B1	*	5/2002	Cyr	2/9
D484,281 S	*	12/2003	Gagnon et al.	D29/110
D487,534 S	*	3/2004	Broersma	D29/108
D497,039 S	*	10/2004	Dehaan et al.	D29/108
6,886,183 B1	*	5/2005	DeHaan et al.	2/6.7
6,938,272 B1	*	9/2005	Brown	2/9

* cited by examiner

Primary Examiner—Ruth McInroy

(57) **CLAIM**

The ornamental design for a mask, as shown and described.

DESCRIPTION

FIG. 1 is a perspective view of a mask showing my new design;

FIG. 2 is a front elevational view thereof;

FIG. 3 is a rear elevational view thereof;

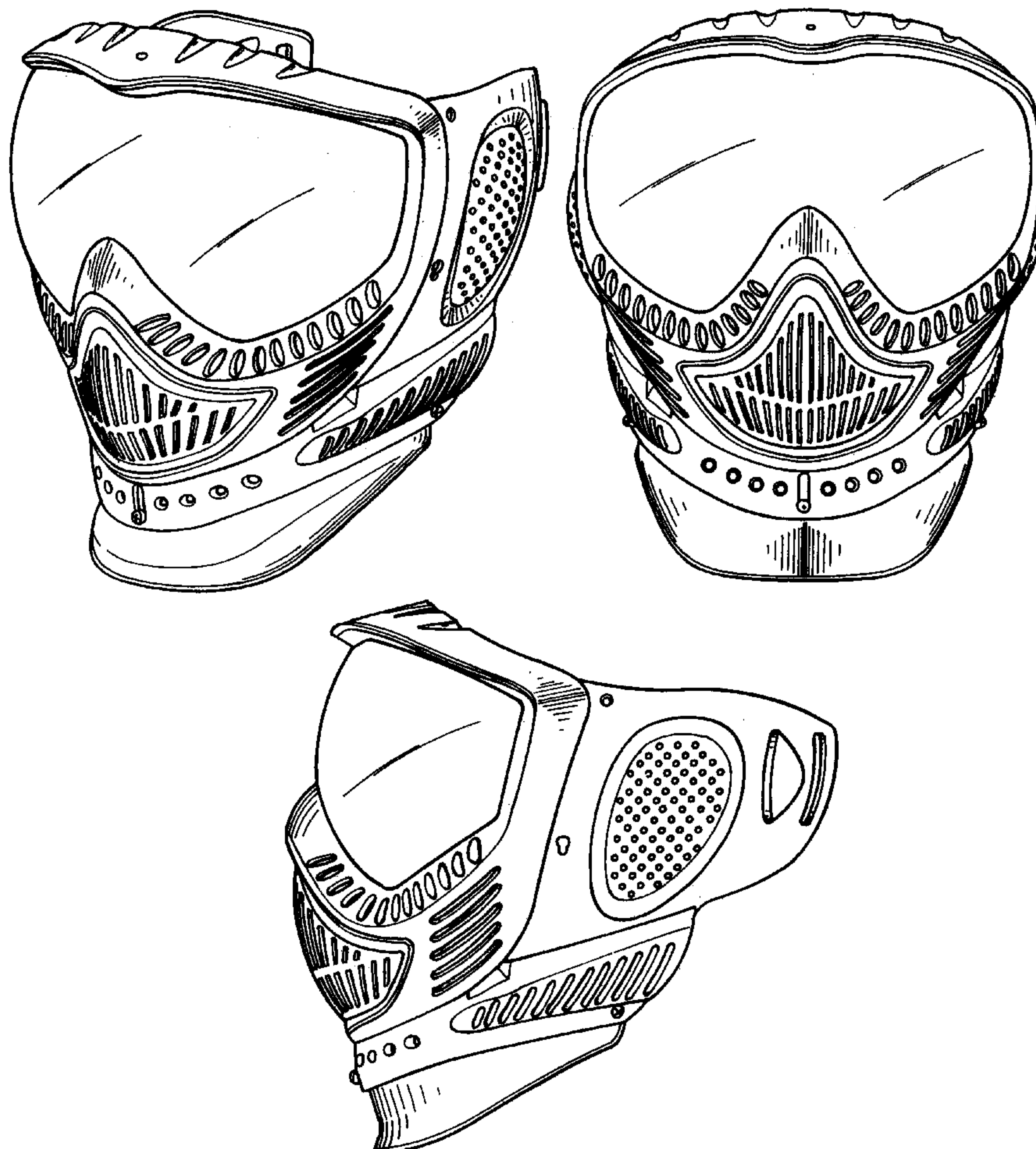
FIG. 4 is a left side elevational view thereof;

FIG. 5 is a right side elevational view thereof;

FIG. 6 is a top plan view thereof; and,

FIG. 7 is a bottom plan view thereof.

1 Claim, 4 Drawing Sheets



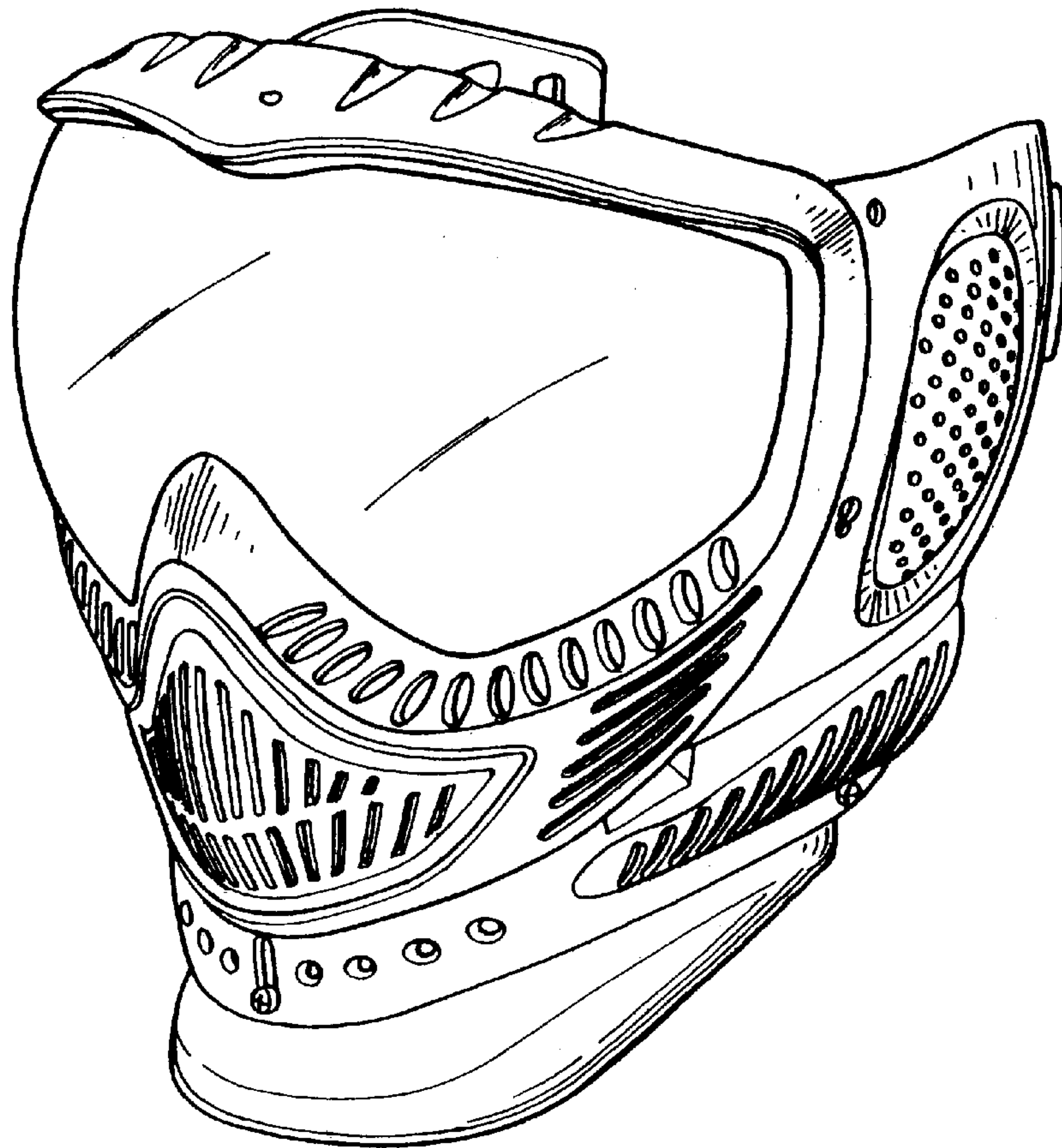


FIG.1

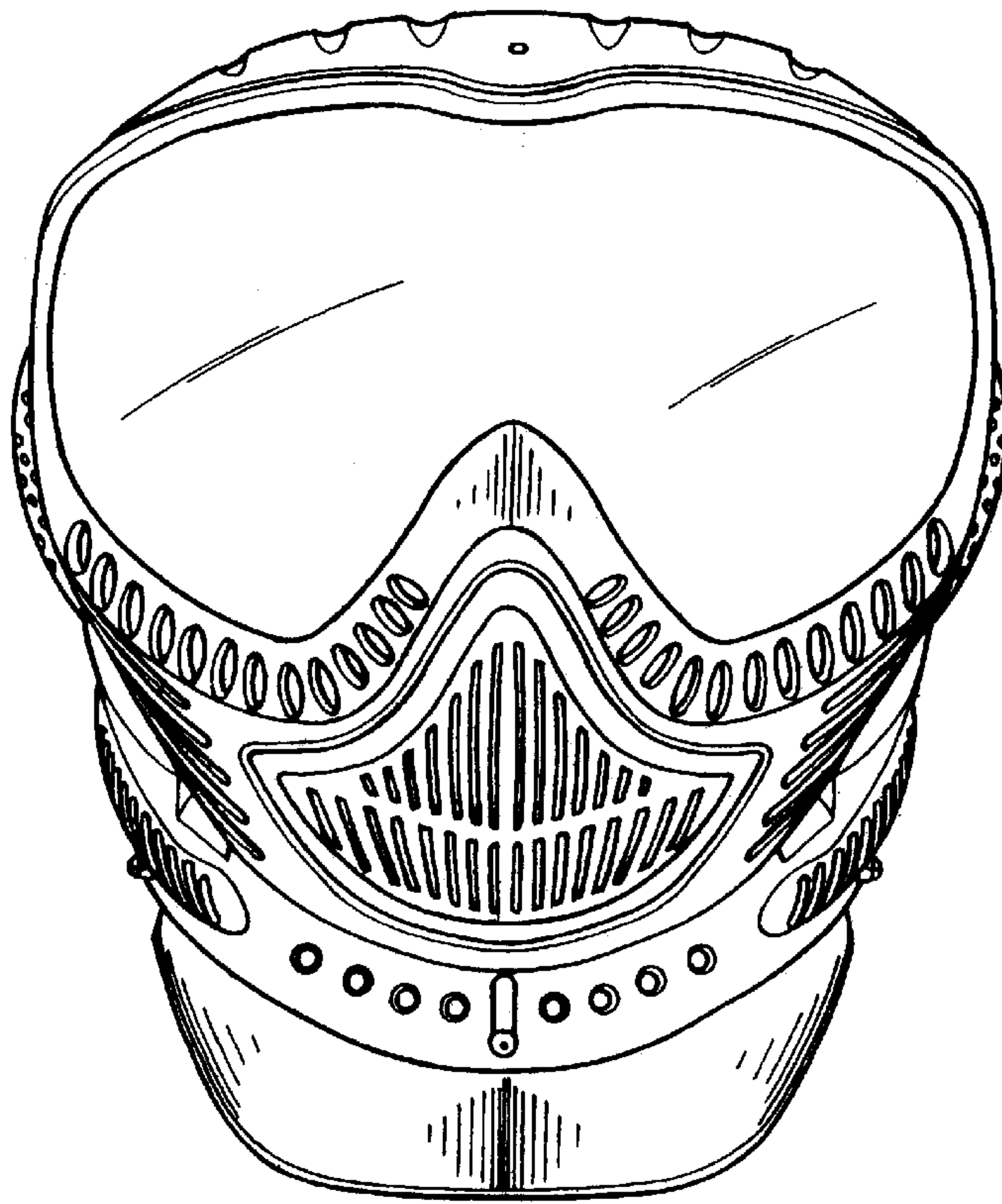


FIG. 2



FIG. 3

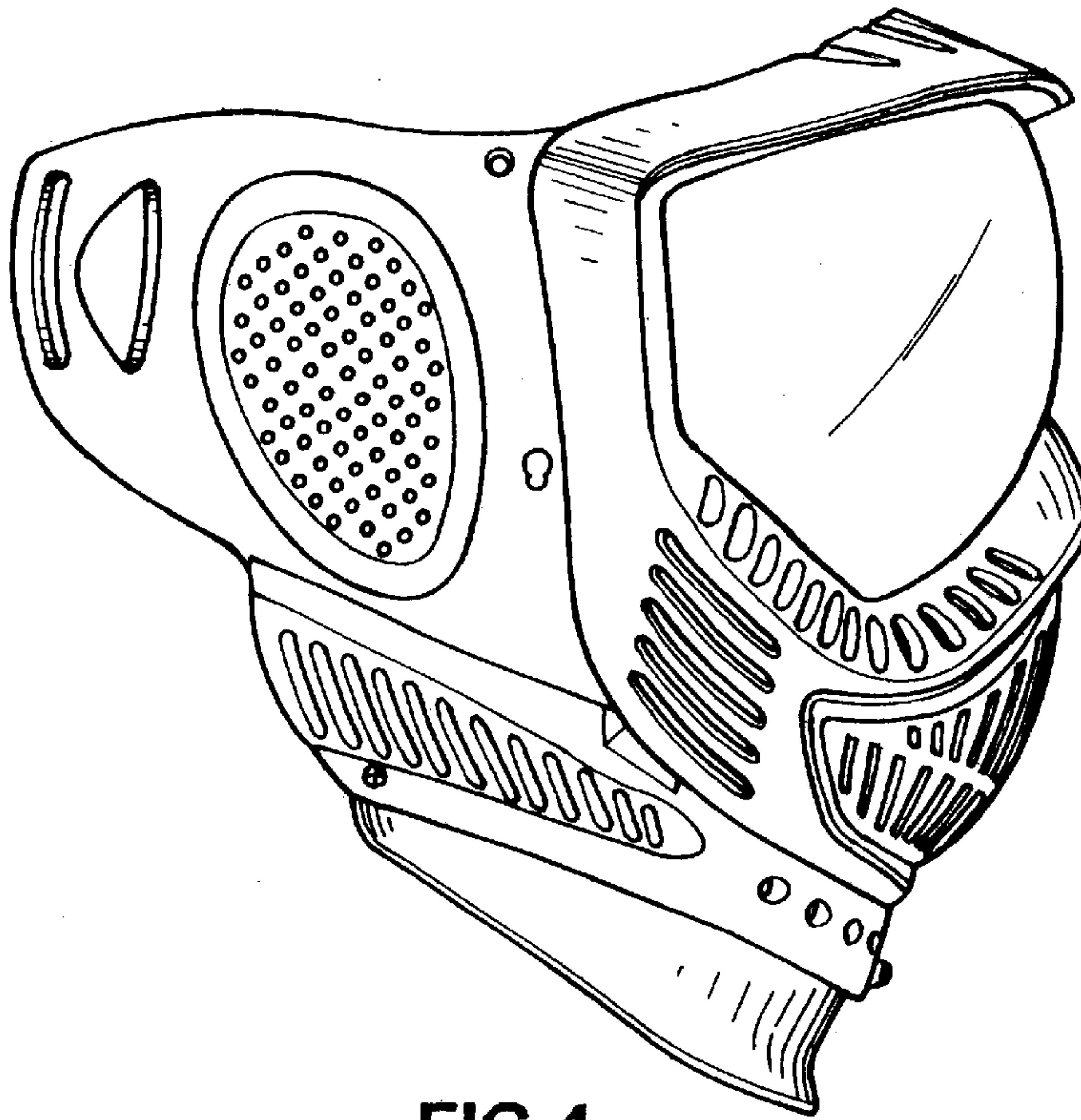


FIG.4

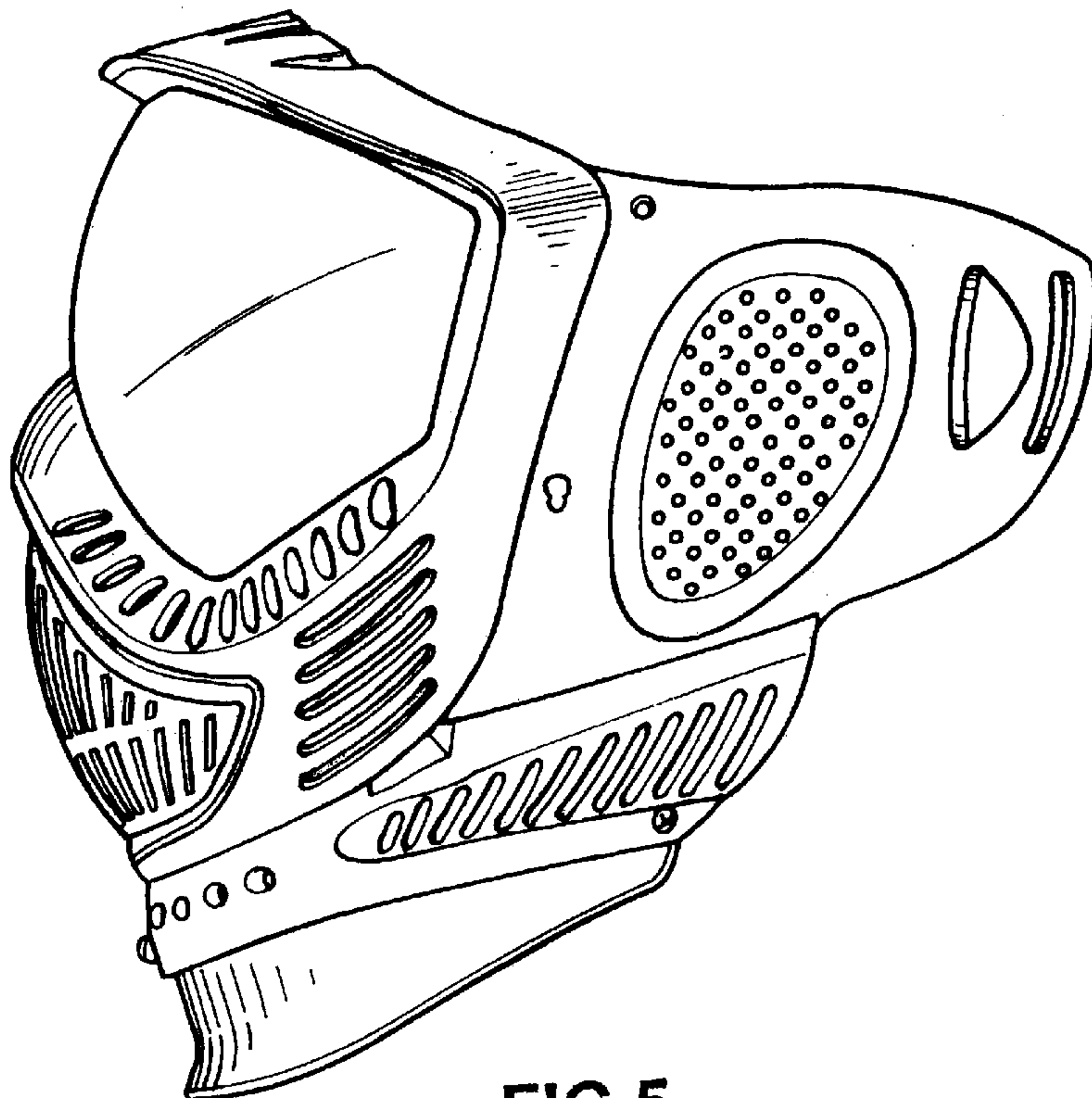


FIG.5

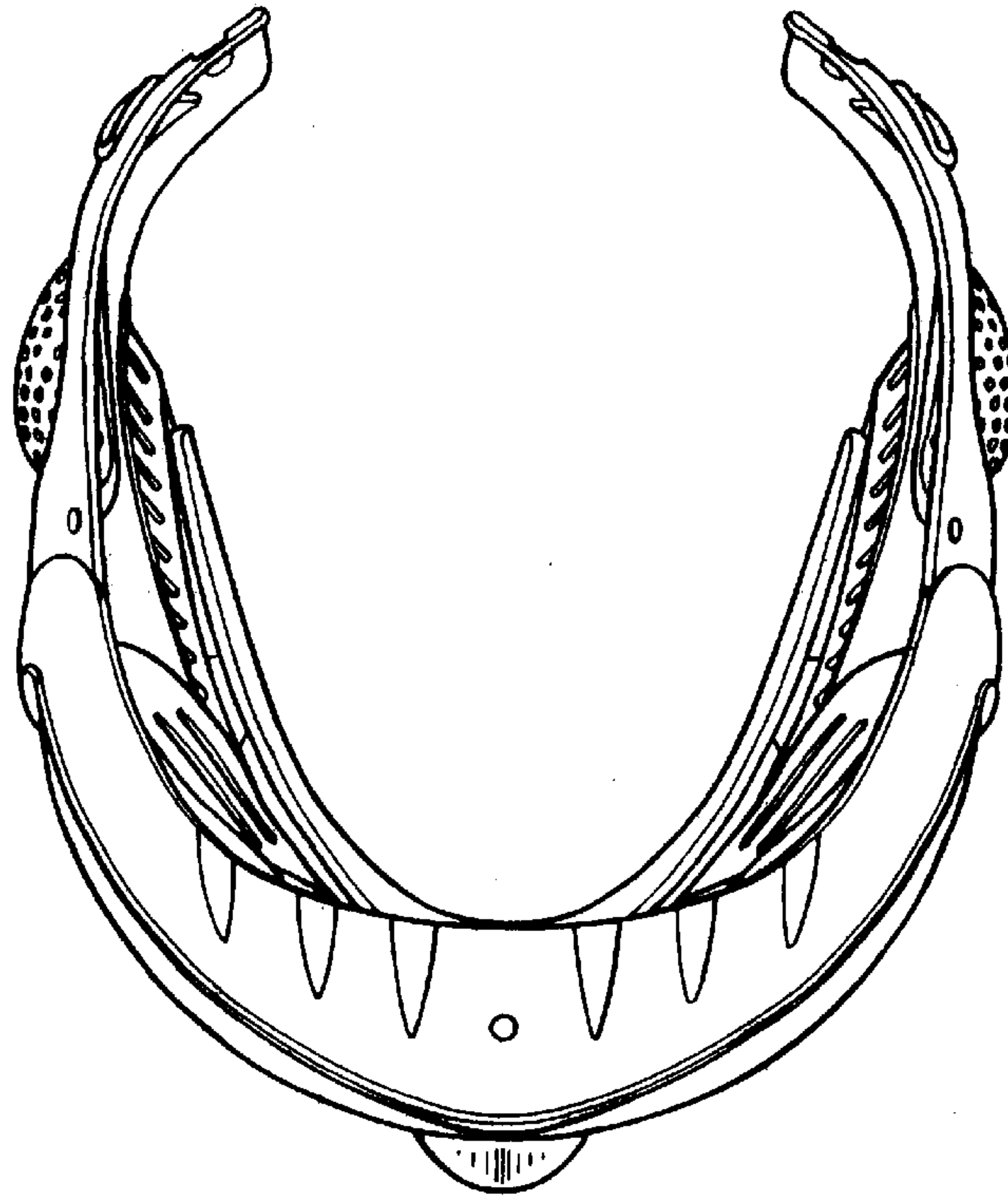


FIG. 6

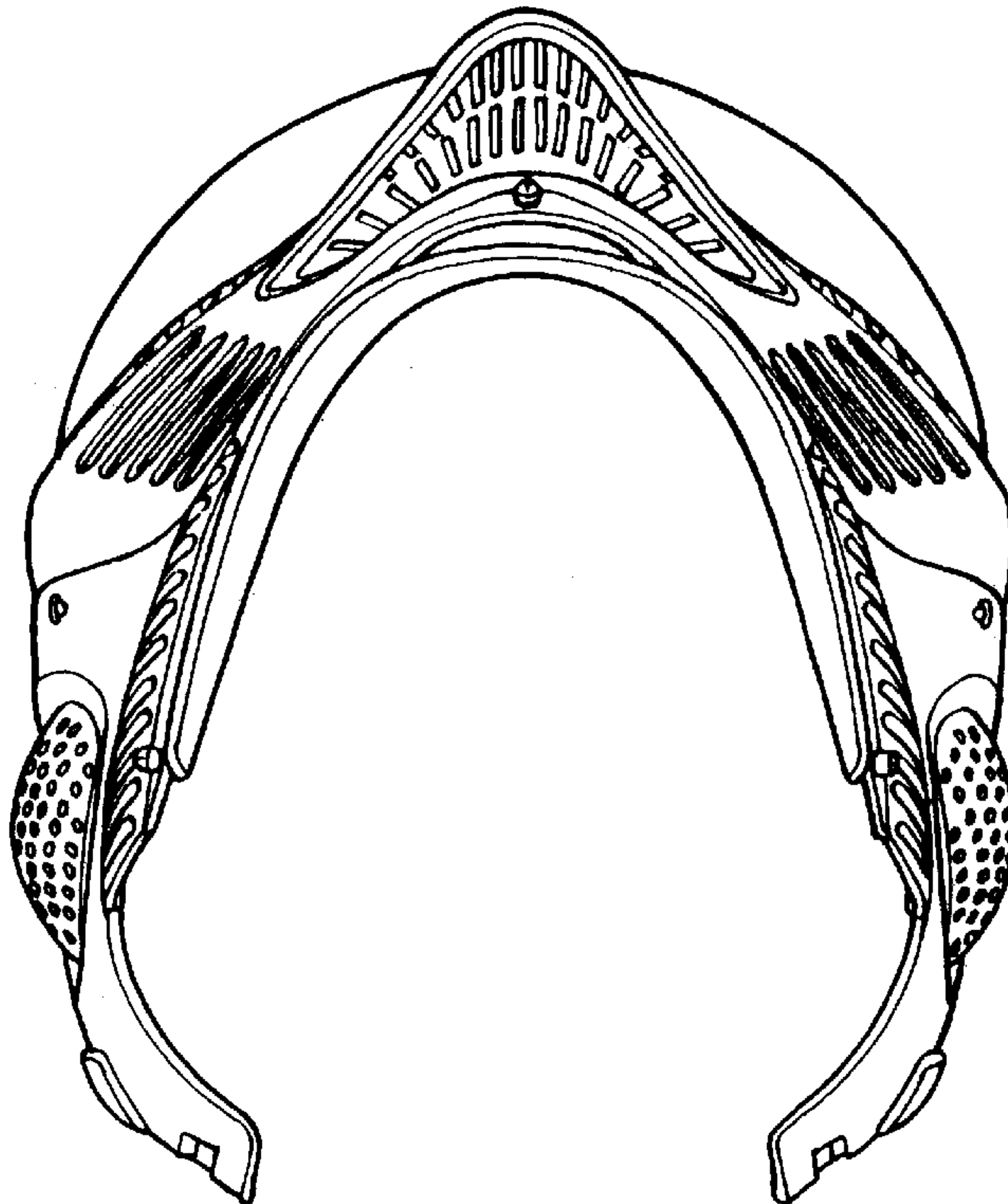


FIG. 7